

CLAIMS

- 207040 9296007
- SUB B3
1. A titanium target for sputtering wherein the oxygen contained in the titanium target for sputtering is 20ppm or less and the average grain diameter of said target is 20 μ m or less.
- SUB B3
2. A titanium target for sputtering wherein the impurity concentration of gas components such as oxygen, nitrogen and hydrogen contained in the titanium target for sputtering is 20ppm or less.
- 10 3. A titanium target for sputtering according to claim 1 or claim 2, wherein the Vickers hardness (Vs) is 120 or less.
4. A titanium target for sputtering according to any one of claims 1 to 3, wherein the total content of alkali metal and alkali earth metal such as Na and K is 5ppm or less, the total
- 15 content of heavy metal and light metal is 10ppm or less, and the total content of radioactive elements such as U and Th is 1ppb or less.
- Add > B4